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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO. 9002	
10/615,554	07/07/2003	Elizabeth Ann Dobisz	HSJ9-2003-0007US1		
75	90 07/27/2005	EXAMINER			
Robert O. Guil	llot, Esq.	CHEN, TIANJIE			
IPLO(R) INTELLECTUA	AL PROPERTY LAW OF	ART UNIT PAPER NUM			
1901 South Bas	•	2652			
Campbell, CA 95008			DATE MAILED: 07/27/2005		

Please find below and/or attached an Office communication concerning this application or proceeding.

		Application N	О.	Applicant(s)				
Office Action Summary		10/615,554		DOBISZ ET AL.				
		Examiner		Art Unit				
		Tianjie Chen		2652				
The MAILING DATE of this Period for Reply	communication app	ears on the co	er sheet with the c	orrespondence ad	ldress			
A SHORTENED STATUTORY PE THE MAILING DATE OF THIS CO - Extensions of time may be available under the after SIX (6) MONTHS from the mailing date - If the period for reply specified above is less to - If NO period for reply is specified above, the re- Failure to reply within the set or extended per - Any reply received by the Office later than three arned patent term adjustment. See 37 CFR	DMMUNICATION. e provisions of 37 CFR 1.13 of this communication. han thirty (30) days, a reply maximum statutory period w iod for reply will, by statute, ee months after the mailing	36(a). In no event, he within the statutory rill apply and will exp cause the applicatio	owever, may a reply be tim minimum of thirty (30) days ire SIX (6) MONTHS from in to become ABANDONED	ely filed s will be considered time the mailing date of this c O (35 U.S.C. § 133).				
Status								
1) Responsive to communicati	on(s) filed on	_•						
2a) This action is FINAL .		action is non-f	inal.					
3) Since this application is in c	3) Since this application is in condition for allowance except for formal matters, prosecution as to the merits is							
closed in accordance with the	closed in accordance with the practice under Ex parte Quayle, 1935 C.D. 11, 453 O.G. 213.							
Disposition of Claims								
4) Claim(s) 1-22 is/are pending 4a) Of the above claim(s) is/are allow 6) Claim(s) 1-22 is/are rejected 7) Claim(s) 1-22 is/are object 8) Claim(s) 1-22 are subject	is/are withdrawed. d. ted to.	vn from consid	·					
Application Papers								
9)☐ The specification is objected	to by the Examine	r.			•			
10)☐ The drawing(s) filed on	D)☐ The drawing(s) filed on is/are: a)☐ accepted or b)☐ objected to by the Examiner.							
Applicant may not request that	Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).							
Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d). 11) The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.								
Priority under 35 U.S.C. § 119								
12) Acknowledgment is made of a) All b) Some * c) No 1. Certified copies of the 2. Certified copies of the 3. Copies of the certified application from the I * See the attached detailed Off	one of: e priority documents priority documents copies of the prior nternational Bureau	s have been re s have been re ity documents ı (PCT Rule 17	ceived. ceived in Application have been received '.2(a)).	on No ed in this National	Stage			
Attachment(s)		۰,۲		(DTO 440)				
 Notice of References Cited (PTO-892) Dotice of Draftsperson's Patent Drawing 	Review (PTO-948)	_		ite				
Information Disclosure Statement(s) (PT Paper No(s)/Mail Date	O-1449 or PTO/SB/08)	5) [6) [Notice of Informal P	atent Application (PT	O-152)			

Non-Final Rejection

Claim Rejections - 35 USC § 102

The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

(e) the invention was described in (1) an application for patent, published under section 122(b), by another filed in the United States before the invention by the applicant for patent or (2) a patent granted on an application for patent by another filed in the United States before the invention by the applicant for patent, except that an international application filed under the treaty defined in section 351(a) shall have the effects for purposes of this subsection of an application filed in the United States only if the international application designated the United States and was published under Article 21(2) of such treaty in the English language.

1. Claims 1-22 are rejected under 35 U.S.C. 102(e) as being anticipated by Gill et al (US 2004/0090718).

Claims 1 and 10, Gill et al shows a hard disk drive including a magnetic head including a read head element in Fig.5, including: a pinned magnetic layer 512 ([0035], line 12); a free magnetic layer 516 having a central portion 536 thereof having a free magnetization; a magnetic bias layer 522 ([0036], line 1), including a central portion 538 thereof that is disposed across the central portion of the free magnetic layer; the central portion of the bias layer being comprised of a material having an approximately zero magnetic moment ([0037], lines 8-13); a barrier layer 540([0043], lines 16-19) being disposed across the central portion of the bias layer.

Claim 19, as described above, Gill et al shows a method for fabricating a magnetic head, including: fabricating a free magnetic layer; fabricating a magnetic bias layer across the free magnetic layer; oxidizing a central portion of the bias layer; depositing an oxygen diffusion barrier layer upon the oxidized central portion of the bias layer.

Claims 2 and 11, Gill et al further shows that the central portion of the bias layer is comprised of an oxidized material ([0043], lines 16-19), and the barrier layer is comprised of a material Rh or Ru, which is inherently a barrier to oxygen diffusion from the central portion of the bias layer ([0043].

Claims 3 and 12, Gill et al shows a thin spacer layer 523 that is disposed upon the free magnetic layer 521, wherein the bias layer 522 is disposed upon the thin spacer layer 523 and the barrier layer 540 is deposed upon the bias layer.

Claims 4 and 13, Gill et al further shows that the barrier layer is comprised of a material that has low electrical conductivity.

Claims 5, 14, and 20; Gill et al further shows that the barrier layer 540 is comprised of Ru or Rh ([0043], lines 13-15).

Claims 6, 7, 15, 16, 21, and 22; Gill et al further shows that the barrier layer has a thickness of approximately 20 Å ([0042], lines 31-33)..

Claims 8 and 17, Gill et al further shows that the thin spacer layer is comprised of a material that is a barrier to oxygen diffusion.

Claims 9 and 18, Gill et al further shows that the thin spacer layer is comprised of Ru ([0042], lines 23-24).

Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

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2. Claims 1- 22 are rejected under 35 U.S.C. 103(a) as being unpatentable over Horng et al (US 2003/0179517) in view of Redon et al (US 6,381,107).

Claims 1 and 10, Horng et al shows a hard disk drive including a magnetic head including a read head element in Fig. 3b, including: a pinned magnetic layer 30 ([0034]); a free magnetic layer 27 having a central portion 10 thereof having a free magnetization; a magnetic bias layer 25, including a central portion thereof that is disposed across the central portion of the free magnetic layer; the central portion of the bias layer being comprised of a material having an approximately zero magnetic moment ([0038] lines 10-14).

Horng et al does not show a barrier layer being disposed across the central portion of the bias layer.

Redon et al shows a magnetic head in Fig. 5 having a barrier layer 75 made of Rh or Ru (Column 5, lines 51-53).

It would have been obvious at the time the invention was made to one of ordinary skill in the art to add the barrier layer 75 into Horng et al's device. The rationale is as follows: Horng teaches a magnetic head with the core portion. It is obvious it has to be sealed for using in a apparatus. Redon et al teaches to add the gap layer 71 and 75 for protecting the core, which is common practice in the art. Redon et al further teaches that the layer 75 can be used for adjusting the distance between the shields (Column 5, lines 53-54). One of ordinary skill I the art would have been motivated to add the barrier layer into Horng et al's device for protecting and adjusting the distance between the shields.

Claim 19, the combination of Horng et al and Redon et al includes a method for fabricating a magnetic head, including: fabricating a free magnetic layer; fabricating a

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magnetic bias layer across the free magnetic layer; oxidizing a central portion of the bias layer; depositing an oxygen diffusion barrier layer upon the oxidized central portion of the bias layer.

Claims 2 and 11, Horng et al further shows that the central portion of the bias layer is comprised of an oxidized material CoFeO ([0038], line 11-13), and the barrier layer is comprised of a material Ru or Rh, which is inherently a barrier to oxygen diffusion from the central portion of the bias layer.

Claims 3 and 12, Horng et al further shows that the magnetic head includes a thin spacer layer 28 that is disposed upon the free magnetic layer, wherein the bias layer is disposed upon the thin spacer layer; in Horng et al and Redon et al's device, the barrier layer is deposed upon the bias layer.

Claims 4 and 13, Redon et al shows that the barrier layer is comprised of a Ru or Rh, which has low electrical conductivity.

Claims 5, 14, and 20; Redon et al shows that the barrier layer is comprised of Ru or Rh.

Claims 6, 15, and 21; Redon et al further shows the barrier layer is comprised of Ru having a thickness of 50 Å (Column 4, line 61-62), which is approximately 40.

Claims 7, 16, and 22; Redon et al shows that the thickness is adjustable (Column 5, lines 53-54). Applicant does not disclose any unexpected result for choosing 20 Å over 50 Å. One of ordinary skill in the art would be able to determine the thickness through experimentation, which would includes the thickness of 20 Å.

Claims 8, 9, 17, and 18; Horng et al shows that the thin spacer layer 28 is comprised of a Ru ([0030]) that is a barrier to oxygen diffusion.

thereof that is disposed across the

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Conclusion

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3. The prior art made of record in PTO-892 Form and not relied upon is

considered pertinent to applicant's disclosure.

4. Any inquiry concerning this communication or earlier communications from the

examiner should be directed to Tianjie Chen whose telephone number is 571-272-

7570. The examiner can normally be reached on 8:00-4:30, Mon-Fri.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's

supervisor, Hoa Nguyen can be reached on 571-272-7579. The fax phone number for

the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the

Patent Application Information Retrieval (PAIR) system. Status information for

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